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Platinum Atomic Layer Deposition on Metal Substrates: A Surface Chemistry Study

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Highlights

- MeCpPtMe₃ adsorption on Ni is self-limiting up to 625 K, grows multilayers at higher Ts.
- O₂ treatment removes all carbon from the surface and grows a thin nickel oxide film on top.

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- Further MeCpPtMe₃ dosing reduces that NiO back to metallic nickel.
- Pt migrates to the layer below the NiO film and mixes with the Ni(0) below.
- Because of that, no Pt films grow on top of Ni by this ALD process.

[‡] Contribution to the special issue in Surface Science entitled "Unraveling Surface Structure and Chemical Pathways: In Honor of Jan Hrbek" Download English Version:

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